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PURE CHEMISTRY

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ROMIL-PUROM™ High Purity Process Solvents Specifications

for industrial applications

Acetic Acid glacial (see Acetic Acid)

Acetic Acid PUROM

P5014

25LT P5014G
200LT P5014D
Dgr H:226-314
P:280c-301+330+331-305+351+338-
307+310



(Acetic Acid glacial)

CH₃COOH MW 60.05 FP 16.7°C BP 117.9°C d 1.05 CAS [64-19-7] Assay >99.8% Water <0.1% Residue <0.0005% Application: High purity process solvent

Acetone PUROM

P5031

25LT P5031G
200LT P5031D
Dgr H:225-319-336-EUH066
P:210-233-305+351+338



(Propanone)

(CH₃)₂COMW 58.08 BP 56.1°C d 0.79 CAS [67-64-1] Assay >99.9% Water <0.2% Residue <0.0005% Application: High purity process solvent

Acetonitrile PUROM

P5048

25LT P5048G
200LT P5048D
Dgr H:225-302+312+332-319
P:210-240-302+352-305+351+338-
403+233



(Methyl Cyanide)

CH₃CNMW 41.05 BP 81.6°C d 0.78 CAS [75-05-8] Assay >99.9% Water <0.01% Residue <0.0005% Application: High purity process solvent

Acetonitrile PUROM

for preparative HPLC

P5046

25LT P5046G
200LT P5046D
Dgr H:225-302+312+332-319
P:210-240-302+352-305+351+338-
403+233



(Methyl Cyanide)

CH₃CNMW 41.05 BP 81.6°C d 0.78 CAS [75-05-8] Assay >99.9% Water <0.03% Residue <0.0005% UV: 230nm >70%; 280nm >95% Application: High purity process solvent for preparative HPLC

n-Butanol (see Butan-1-ol)

n-Butyl Alcohol (see Butan-1-ol)

tert-Butyl Methyl Ether (see Methyl tert-Butyl Ether)

Butan-1-ol PUROM

P5083

25LT P5083G
200LT P5083D
Dgr H:226-302-315-318-335-336
P:210-280F-302+352-304+340-
305+351+338-313



(n-Butanol, n-Butyl Alcohol)

CH₃(CH₂)₃OH MW74.12 BP 117.7°C d 0.81 CAS [71-36-3] Assay >99.8% Water <0.05% Residue <0.0005% Application: High purity process solvent

Chloroform PUROM

stabilised with amylene

P5140

200LT P5140D
Dgr H:351-361d-331-302-372-319-
315
P:261v-280F-304+340-305+351+338-
308+313



(Trichloromethane)

CHCl₃ MW119.38 BP 61.2°C d 1.48 CAS [67-66-3] Assay >99.9%* Water <0.005% Residue <0.0005% *ex stabiliser Stabiliser: Amylene ca. 25 ppm Application: High purity process solvent

Chloroform PUROM

stabilised with ethanol

P5135

200LT P5135D
Dgr H:351-361d-331-302-372-319-
315
P:261v-280F-304+340-305+351+338-
308+313



(Trichloromethane)

CHCl₃ MW119.38 BP 61.2°C d 1.48 CAS [67-66-3] Assay >99.9%* Water <0.005% Residue <0.0005%

*ex stabiliser Stabiliser: Ethanol ca. 1% w/w

Stabiliser should only be removed immediately before use by adsorption onto activated alumina.

Application: High purity process solvent





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Dichloromethane PUROM

stabilised with amylene

P5202

25LT P5202G
200LT P5202D
Wng H:351
P:281-308+313



(Methylene Dichloride)

CH₂Cl₂MW84.93BP 39.6°C d 1.33 CAS [75-09-2]
Assay >99.9%* Water <0.01% Residue <0.0005%
*ex stabiliser Stabiliser: Amylene ca. 25 ppm
Application: Highpurity processsolvent

Diethyl Ether PUROM

stabilised with BHT

P5220

25LT P5220G
200LT P5220D
Dgr H:224-302-336-EUH019-EUH066
P:210-240-403+235



(C₂H₅)₂O MW 74.12 BP 34.4°C d 0.71 CAS [60-29-7] Assay >99.9%*
Water <0.02% Residue <0.0005%* *ex stabiliser Peroxides (at time of
manufacture) <0.0001% (<1 ppm) Stabiliser: Butylated hydroxytoluene
(BHT) ca. 5 ppm Application: High purityprocesssolvent

1,2-Dimethoxyethane PUROM

P5261

25LT P5261G
200LT P5261D
Dgr H:25-360FD-332- EUH019
P:201-210-308+313- 403+235



(Ethylene Glycol Dimethyl Ether)

CH₃OCH₂CH₂OCH₃ MW90.12 FP -58°C BP 85°C d 0.87 CAS [110-71-4]
Assay >99.9% Water <0.01% Residue <0.0005% Peroxides (at time of
manufacture) <0.0001% (<1 ppm) Application: High purity process
solvent

Dimethylformamide PUROM

P5253

25LT P5253G
200LT P5253D
Dgr H:360D-226-312+332-319
P:201-210-302+352-305+351+338-
308+313



HCON(CH₃)₂ MW 73.09 BP 153.0°C d 0.95CAS[68-12-2]
Assay >99.9% Water <0.03% Residue <0.0005%
Application: High purity process solvent

1,4-Dioxan PUROM

P5297

25LT P5297G
200LT P5297D
Dgr H:225-350-319-335-EUH019-
EUH066
P:210-281-305+351+338-308+313



C₄H₈O₂MW 88.11 FP 11.8°C BP101.3°C d 1.03 CAS [123-91-1]
Assay >99.9% Water <0.005% Residue <0.0005% Unstabilised
Peroxides (at time of manufacture) <0.0001% (<1 ppm)
Application: High purity process solvent

Ethyl Alcohol (see Ethanol)

Ethylene Glycol Dimethyl Ether (see 1,2-Dimethoxyethane)

Ethanol absolute PUROM

P5314

25LT P5314G
200LT P5314D
Dgr H:225
P:210-233-240-403+235



(Ethyl Alcohol)

C₂H₅OHMW 46.07 BP 78.3°C d 0.79 CAS [64-17-5]
Assay >99.8% Water <0.1% Residue <0.0005%
Application: High purity process solvent

Ethyl Acetate PUROM

P5346

25LT P5346G
200LT P5346D
Dgr H:225-319-336-EUH066
P:210-233-240-305+351+338-
403+235



CH₃COOC₂H₅ MW 88.11 BP 77.1°Cd 0.90 CAS [141-78-6]
Assay >99.9% Water <0.005% Residue <0.0005%
Application: High purity process solvent

n-Heptane 95% PUROM

P5367

25LT P5367G
200LT P5367D
Dgr H:225-304-315-336-410
P:210-273-301+310-331-302+352-
304+340-403+235



CH₃(CH₂)₅CH₃ MW 100.21BP94-98°Cd 0.68 CAS [142-82-5]
Water <0.005% Residue <0.0005% Assay (n-isomer) >95%
Assay (all isomers) >99.5% Application: High purity process
solvent





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n-Heptane 99% PUROM

P5366

25LT P5566G
200LT P5566D
Dgr H:225-304-315-336-410
P:210-273-301+310-331-302+352-304+340-403+235



CH₃(CH₂)₅CH₃MW 100.21 BP98.4°C d0.68 CAS [142-82-5]
Assay >99% Water <0.005% Residue <0.0005%
Application: High purity process solvent

Hexane fraction PUROM

P5390

25LT P5390G
200LT P5390D
Dgr H:225-304-361f-373-315-336-411
P:210-240-273-301+310-331-302+352-403+235



C₆H₁₄ BP 65-70°C d 0.66 CAS [73513-42-5] Water <0.005% Residue <0.0005% Comprises ca. 50% n-isomer, the remainder being predominantly other isomers of hexane. Application: High purity process solvent

iso-Hexane 95% PUROM

P5388

25LT P5388G
200LT P5388D
Dgr H:225-304-315-336-411
P:233-273-301+310-331-302+352-403+235



C₆H₁₄ MW86.18BP55-63°Cd0.65CAS[107-83-5]
Water <0.005% Residue <0.0005%
n-Hexane <5%
Application: High purity process solvent

n-Hexane 95% PUROM

P5389

25LT P5389G
200LT P5389D
Dgr H:225-304-361f-373-315-336-411
P:210-240-273-301+310-331-302+352-403+235



CH₃(CH₂)₄CH₃ MW 86.18BP67-70°Cd 0.66 CAS [110-54-3]
Water <0.005% Residue <0.0005%
Assay (n-isomer) >95%
Assay (all isomers) >99.5%
Application: High purity process solvent

Methyl Alcohol (see Methanol)

Methyl Cyanide (see Acetonitrile)

Methylene Dichloride (see Dichloromethane)

4-Methylpentan-2-one (see Methyl iso-Butyl Ketone)

Methanol PUROM

P5410

25LT P5410G
200LT P5410D
Dgr H:225-301+311+331-370
P:210-280f-302+352-309+310-403+235



(Methyl Alcohol)
CH₃OHMW 32.04 BP 64.5°C d 0.79 CAS [67-56-1]
Assay >99.9% Water <0.02% Residue <0.0005%
Application: High purity process solvent

Methanol PUROM

for preparative HPLC

P5408

25LT P5408G
200LT P5408D
Dgr H:225-301+311+331-370
P:210-280f-302+352-309+310-403+235



(Methyl Alcohol)
CH₃OHMW 32.04 BP 64.5°C d 0.79 CAS [67-56-1] Assay >99.8% Water <0.05% Residue <0.0005% UV: 225nm >50%; 255nm >95% Application: High purity process solvent for preparative HPLC

Methyl tert-Butyl Ether PUROM

P5447

25LT P5447G
200LT P5447D
Dgr H:225-315
P:210-233-302+352-403+235



(tert-Butyl Methyl Ether)
CH₃OC(CH₃)₃ MW 88.15 BP 55.4°C d 0.74 CAS [1634-04-4] Assay >99.7% Water <0.02% Residue <0.0005% Peroxides (at time of manufacture) <0.0001% (<1 ppm)
Application: High purity process solvent

2-Methyltetrahydrofuran PUROM

P5536

25LT P5536G
200LT P5536D
Dgr H:225-319-335-EUH019
P:210-233-240-305+351+338-403+235



CH₃C₄H₇OMW86.13 BP80°Cd0.86 CAS[96-47-9] As say >99.8% Water <0.01% Residue <0.0005% Unstabilised Peroxides (at time of manufacture) <0.0001% (<1 ppm)
Application: High purity process solvent



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2-Methyltetrahydrofuran PUROM

stabilised with BHT

P5537

25LT P5537G
200LT P5537D
Dgr H:225-319-335-EUH019
P:210-233-240-305+351+338-403+235
CH₃C₄H₇O MW 86.13 BP 80°C d 0.86 CAS [96-47-9]
Assay >99.8%* Water <0.01% Residue <0.0005%* *ex
stabiliser Peroxides (at time of manufacture) <0.0001%
(<1 ppm) Stabiliser: Butylated hydroxytoluene (BHT) ca.
250 ppm Application: High purity process solvent



iso-Octane (see 2,2,4-Trimethylpentane)

Perchloroethylene (see Tetrachloroethylene)

Petroleum Distillate (see Petroleum Ether)

Petroleum Spirit (see Petroleum Ether)

n-Propanol (see Propan-1-ol)

iso-Propanol (see Propan-2-ol)

Propanone (see Acetone)

n-Propyl Alcohol (see Propan-1-ol)

iso-Propyl Alcohol (see Propan-2-ol)

n-Pentane 95% PUROM

P5571

25LT P5571G
200LT P5571D
Dgr H:225-304-336-411-EUH066
P:273-301+310-331-403+235
CH₃(CH₂)₃CH₃ MW 72.15BP35.5-37°Cd 0.63 CAS [109-66-0]
Water <0.005% Residue <0.0005%
Assay (n-isomer) >95%
Assay (all isomers) >99.5%
Application: High purity process solvent



Petroleum Ether 40-60°C PUROM

P5601

25LT P5601G
200LT P5601D
Dgr H:225-304-336-411-EUH066
P:210-233-243-273-280-301+310-303+361+353-304+340-331-403+235
(Petroleum Distillate, Petroleum Spirit)
BP40-60°C d 0.64 CAS [8032-32-4] Water <0.005%
Residue <0.0005% Application: High purity process
solvent



Petroleum Ether 60-80°C PUROM

P5602

25LT P5602G
200LT P5602D
Dgr H:225-304-315-336-411
P:210-243-273-280-301+310-331-403+235
(Petroleum Distillate, Petroleum Spirit)
BP60-80°C d 0.67 Water <0.005% Residue <0.0005%
Application: High purity process solvent



Propan-1-ol PUROM

P5624

25LT P5624G
200LT P5624D
Dgr H:225-318-336
P:210-233-280F-305+351+338-313
(n-Propanol, n-Propyl Alcohol)
CH₃CH₂CH₂OH MW 60.10 BP 97.2°C d 0.80 CAS [71-23-8]
Assay >99.9% Water <0.05% Residue <0.0005%
Application: High purity process solvent



Propan-2-ol PUROM

P5625

25LT P5625G
200LT P5625D
Dgr H:225-319-336
P:210-233-305+351+338
(iso-Propanol, iso-Propyl Alcohol)
(CH₃)₂CHOH MW 60.10 BP 82.2°C d 0.78 CAS [67-63-0]
Assay >99.9% Water <0.02% Residue <0.0005%
Application: High purity process solvent





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Trichloromethane (see Chloroform)

Tetrachloroethylene PUROM

(Perchloroethylene)

P5702

25LT P5702G
200LT P5702D
Wng H:315-317-319-336-351-411
P:273-281-302+352-305+351+338-308+313



CCl₂CCl₂MW 165.83 BP 121.1°C d 1.62 CAS [127-18-4]
Assay >99.9% Water <0.005% Residue <0.0005%
Unstabilised
Application: High purity process solvent

Tetrahydrofuran PUROM

P5718

25LT P5718G
200LT P5718D
Dgr H:225-319-335-351-EU019
P:210-240-305+351+338-308+313-403+233



CH₂(CH₂)₂CH₂OMW 72.11BP 66.0°C d0.89 CAS [109-99-9]
Assay >99.9% Water <0.005% Residue <0.0005%
Unstabilised Peroxides (at time of manufacture) <0.0001% (<1 ppm) Application: High purity process solvent

Tetrahydrofuran PUROM

stabilised with BHT

P5719

25LT P5719G
200LT P5719D
Dgr H:225-319-335-351-EU019
P:210-240-305+351+338-308+313-403+233



CH₂(CH₂)₂CH₂O MW 72.11 BP 66.0°C d 0.89 CAS [109-99-9]
Assay >99.9%* Water <0.005% Residue <0.0005%* *ex stabiliser Peroxides (at time of manufacture) <0.0001% (<1 ppm) Stabiliser: Butylated hydroxytoluene (BHT) ca. 250 ppm
Application: High purity process solvent

Toluene PUROM

P5771

25LT P5771G
200LT P5771D
Dgr H:225-304-315-336-361d-373
P:210-240-301+310-331-302+352-403+235



C₆H₅CH₃MW 92.14 BP 110.6°C d 0.87 CAS [108-88-3]
Assay >99.9% Water <0.01% Residue <0.0005%
Application: High purity process solvent

2,2,4-Trimethylpentane PUROM

P5901

25LT P5901G
200LT P5901D
Dgr H:225-304-315-336-410
P:210-233-240-273-301+310-331-302+352-304+340-403+235



(iso-Octane)
(CH₃)₃CCH₂CH(CH₃)₂ MW 114.23 BP 99.2°C d 0.69 CAS [540-84-1]
Assay >99.75% Water <0.005% Residue <0.0005%
Application: High purity process solvent

Water PUROM

P5950

25LT P5950G
200LT P5950D

H₂OMW 18.02 FP 0.0°C BP 100.0°C CAS [7732-18-5] Residue <0.0001% Resistivity (at time of manufacture) >18 MOhm @ 25°C pH (at time of manufacture) 5.5-8.0 @ 25°C Application: High purity process solvent

Water PUROM

for preparative HPLC

P5948

25LT P5948G
200LT P5948D

H₂O MW 18.02 FP 0.0°C BP 100.0°C d 1.00 CAS [7732-18-5] Residue <0.0005% Resistivity (at time of manufacture) >18 MOhm @ 25°C pH (at time of manufacture) 5.5-8.0 @ 25°C TOC (at time of manufacture) <50 ppb Application: High purity process solvent for preparative HPLC

Xylene mixed isomers PUROM

P5982

25LT P5982G
200LT P5982D
Wng H:226-312+332-315 P:210-302+352-304+340



C₆H₄(CH₃)₂ MW106.17BP138-142°Cd0.86CAS[1330-20-7]
Water <0.01% Residue <0.0005%
Comprises 3 isomers and ethylbenzene
Assay (total C₈H₁₀ isomers) >98.5%
Ethylbenzene typically <3%
Toluene typically <0.5%
Methylethylbenzene typically <0.5%
Application: High purity process solvent





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25LT P5702G 200LT P5702D Wng H:315-317-319-336-351-411 P:273-281-302+352-305+351+338-308+313	Trichloromethane (see Chloroform) Tetrachloroethylene PUROM (Perchloroethylene) CCl ₂ CCl ₂ MW 165.83 BP 121.1°C d 1.62 CAS [127-18-4] Assay >99.9% Water <0.005% Residue <0.0005% Unstabilised Application: High purity process solvent	P5702
25LT P5718G 200LT P5718D Dgr H:225-319-335-351-EUH019 P:210-240-305+351+338-308+313-403+233	Tetrahydrofuran PUROM CH ₂ (CH ₂) ₂ CH ₂ OMW 72.11BP 66.0°C d0.89 CAS [109-99-9] Assay >99.9% Water <0.005% Residue <0.0005% Unstabilised Peroxides (at time of manufacture) <0.0001% (<1 ppm) Application: High purity process solvent	P5718
25LT P5719G 200LT P5719D Dgr H:225-319-335-351-EUH019 P:210-240-305+351+338-308+313-403+233	Tetrahydrofuran PUROM stabilised with BHT CH ₂ (CH ₂) ₂ CH ₂ O MW 72.11 BP 66.0°C d 0.89 CAS [109-99-9] Assay >99.9%* Water <0.005% Residue <0.0005%* *ex stabiliser Peroxides (at time of manufacture) <0.0001% (<1 ppm) Stabiliser: Butylated hydroxytoluene (BHT) ca. 250 ppm Application: High purity process solvent	P5719
25LT P5771G 200LT P5771D Dgr H:225-304-315-336-361d-373 P:210-240-301+310-331-302+352-403+235	Toluene PUROM C ₆ H ₅ CH ₃ MW 92.14 BP 110.6°C d 0.87 CAS [108-88-3] Assay >99.9% Water <0.01% Residue <0.0005% Application: High purity process solvent	P5771
25LT P5901G 200LT P5901D Dgr H:225-304-315-336-410 P:210-233-240-273-301+310-331-302+352-304+340-403+235	2,2,4-Trimethylpentane PUROM (<i>iso-Octane</i>) (CH ₃) ₃ CCCH ₂ CH(CH ₃) ₂ MW 114.23 BP 99.2°C d 0.69 CAS [540-84-1] Assay>99.75%Water <0.005% Residue<0.0005% Application:Highpurityprocess solvent	P5901
25LT P5950G 200LT P5950D	Water PUROM H ₂ OMW 18.02 FP 0.0°C BP 100.0°C CAS [7732-18-5] Residue <0.0001% Resistivity (at time of manufacture) >18 MOhm @ 25°C pH (at time of manufacture) 5.5-8.0 @ 25°C Application: High purity process solvent	P5950
25LT P5948G 200LT P5948D	Water PUROM for preparative HPLC H ₂ O MW 18.02 FP 0.0°C BP 100.0°C d 1.00 CAS [7732-18-5] Residue <0.0005% Resistivity (at time of manufacture) >18 MOhm @ 25°C pH (at time of manufacture) 5.5-8.0 @ 25°C TOC (at time of manufacture) <50 ppb Application: High purity process solvent for preparative HPLC	P5948
25LT P5982G 200LT P5982D Wng H:226-312+332-315 P:210-302+352-304+340	Xylene mixed isomers PUROM C ₆ H ₄ (CH ₃) ₂ MW106.17BP138-142°Cd0.86CAS[1330-20-7] Water <0.01% Residue <0.0005% Comprises 3 isomers and ethylbenzene Assay (total C ₈ H ₁₀ isomers) >98.5% Ethylbenzene typically <3% Toluene typically <0.5% Methylethylbenzene typically <0.5% Application: High purity process solvent	P5982